

Applicant(s): Hiroyuki UWAZUMI et al.  
Atty. Docket No.: 32307-198189

**IN THE TITLE:**

**Please replace the title with the following new title:**

SPUTTERING TARGET FOR PRODUCTION OF A MAGNETIC RECORDING  
MEDIUM

**IN THE SPECIFICATION**

**Please delete the first paragraph on page 1, please add as the first paragraph on page 1 the following:**

**CROSS REFERENCE TO RELATED APPLICATIONS**

This application is a divisional application of Application No. 09/789,928 filed February 22, 2001, which claims priority of the commonly owned Japanese application Serial No. 2000-046471 filed February 23, 2000. The disclosure of the above-referenced patent applications, as well as that of each US and foreign patent and patent application identified in the specification of the present application, is incorporated herein by reference.

**Delete the paragraph at page 2, lines 12-21 and replace it with the following paragraph:**

Examples using the granular magnetic layer are shown in Japanese patent Application Laid-open No. 8-255342 (1996) and U.S. Patent No. 5,679,473, Japanese Patent Application Laid-open No. 8-255342 (1996) proposed the achievement of a low noise by laminating a nonmagnetic film, a ferromagnetic film, and a nonmagnetic film sequentially and then heat treating the laminate to form a granular recording layer comprising ferromagnetic crystal grains dispersed in the nonmagnetic film. In this case, a silicon oxide or nitride is used as the nonmagnetic film.